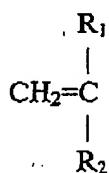


CLAIM AMENDMENTS

1. (Currently Amended) A nail enamel composition comprising, by weight of the total composition:

10-95% solvent, and

5-95% of a polymer capable of forming a film on the nail, having a glass transition temperature in the range of 5 to 90° C., obtained by polymerizing at least two different types of monomers wherein one monomer is a nonpolar ethylenically unsaturated monomer and the other monomer is a polar monomer of the formula:



wherein R₁ is H, or a C₁₋₃₀ straight or branched chain alkyl, aryl, or aralkyl; and R₂ is COOM wherein M is H; (CH₂R₁)_nOH; (CH₂CH₂O)_nH; (CH₂)_nNR₁; (CH₂R₁)CONR₁H) where n is 1-100, and wherein the polar monomer is present at about 2 to 29% by weight of the total polymer; wherein said polymer is substantially free of monomers containing acetoacetoxy moieties.

2. (Original) The composition of claim 1 wherein the solvent is aqueous.

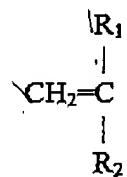
3. (Original) The composition of claim 1 wherein the comprises a non-aqueous solvent.

4. (Original) The composition of claim 3 wherein the non-aqueous solvent is an aliphatic or aromatic ketone; aliphatic or aromatic alcohol; glycol ether; ester, or mixtures thereof.

5. (Original) The composition of claim 1 wherein the film forming polymer the polar monomer is anionically or cationically charged.

6. (Original) The composition of claim 5 wherein the polar monomer is anionically charged.

7. (Original) The composition of claim 6 wherein the polar monomer has the general formula:



wherein R_1 is H, or a C_{1-30} straight or branched chain alkyl, aryl, or aralkyl; and R_2 is $COOM$

wherein M is H; $(CR_1)_nOH$; $(CH_2CH_2O)_nH$; $(CH_2)_nNR_1$; where n is 1-100.

8. (Original) The composition of claim 7 wherein the polar monomer, R_1 is H or CH_3 , and R_2 is $COOM$ wherein M is H.

9. (Original) The composition of claim 8 wherein the polar monomer is acrylic acid.

10. (Original) The composition of claim 1 further comprising 0.1-30% by weight of the total composition of pigment.

11. (Original) The composition of claim 1 further comprising 0.01-15% by weight of the total composition of a suspending agent.

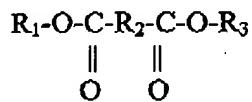
12. (Original) The composition of claim 11 wherein the suspending agent is a montmorillonite mineral or associative thickener.

13. (Original) The composition of claim 1 further comprising 0.01-10% by weight of the total composition of a silicone glycol copolymer defoaming agent.

14. (Original) The composition of claim 1 further comprising 0.1-35% by weight of the total composition of one or more plasticizers.

15. (Original) The composition of claim 14 wherein the plasticizer comprises a glyceryl, glycol, or citrate ester.

16. (Original) The composition of claim 14 wherein the plasticizers comprises a compound of the general formula:



wherein R₁, R₂, and R₃ are each independently a C₁₋₂₀ straight or branched chain alkyl or alkylene which may be substituted with one or more hydroxyl groups.

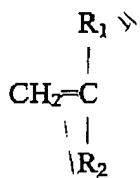
17. (Currently Amended) A two container kit for polishing nails comprising:

(a) a first container containing a nail enamel composition comprising, by weight of the total composition:

10-95% solvent, and

5-95% of a film forming polymer having a glass transition temperature in the range of 5 to 90° C. obtained by polymerizing at least two different types of monomers wherein one

monomer is a nonpolar ethyl nically unsaturated monomer and the other monomer is a polar monomer of the formula:



wherein R_1 is H, or a C_{1-30} straight or branched chain alkyl, aryl, or aralkyl; and R_2 is COOM wherein M is H; $(\text{CH}_2\text{R}_1)_n\text{OH}$; $(\text{CH}_2\text{CH}_2\text{O})_n\text{H}$; $(\text{CH}_2)_n\text{NR}_1$; $(\text{CH}_2\text{R}_1\text{CONR}_1\text{H})$ where n is 1-100, and wherein the polar monomer is present at about 2 to 29% by weight of the total polymer; wherein said polymer is substantially free of monomers containing acetoacetoxy moieties; and

(b) a second container containing a nail enamel topcoat composition comprising, by weight of the total topcoat composition:

1-99% solvent, and

1-99% of a film forming polymer.

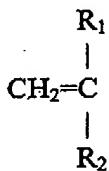
18. (Currently Amended) The kit of claim 17 wherein the film forming polymer in the second container comprises a cellulosic based film former.

19. (Currently Amended) A method for polishing the nails comprising:

(a) applying to the nails a first composition comprising, by weight of the total composition:

10-95% solvent, and

5-95% of a film forming polymer having a glass transition temperature in the range of 5 to 90° C. obtained by polymerizing at least two different types of monomers wherein one monomer is a nonpolar ethylenically unsaturated monomer and the other monomer is a polar monomer of the formula:



wherein R₁ is H, or a C₁₋₃₀ straight or branched chain alkyl, aryl, or aralkyl; and R₂ is COOM wherein M is H; (CHR₁)_nOH; (CH₂CH₂O)_nH; (CH₂)_nNR₁; (CHR₁CONR₁H) where n is 1-100, and wherein the polar monomer is present at about 2 to 29% by weight of the total polymer; and wherein said polymer is substantially free of monomers containing acetoacetoxy moieties; and

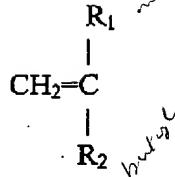
(b) applying to the nails a second composition comprising, by weight of the total composition:

1.99% solvent, and

1.99% of a film forming polymer; wherein the dried film formed by (a) and (b) resides on the nails for five to ten days.

20. Cancelled.

21. (Previously Added) The composition of claim 1 wherein the ethylenically unsaturated nonpolar monomer is a monofunctional monomer having the formula:



wherein R₁ is H, a C₁₋₃₀ straight or branched chain alkyl, aryl, aralkyl; R₂ is H, CH₃, a pyrrolidone, or a substituted or unsubstituted aromatic, alicyclic, or bicyclic ring where the substitutents are C₁₋₃₀ straight or branched chain alkyl, or COOM wherein M is a C₁₋₃₀ straight or branched chain alkyl, pyrrolidone, or a substituted or unsubstituted aromatic, alicyclic, or bicyclic ring where the substitutents are C₁₋₃₀ straight or branched chain alkyl which may be substituted with one or more halogens.

22. (Currently Amended) The composition of claim 22 21 wherein R₁ in the nonpolar monomer is H or a C₁₋₃₀ straight or branched chain alkyl, and R₂ in the nonpolar monomer is COOM wherein M is a C₁₋₃₀ straight or branched chain alkyl.

23. (Previously Added) The composition of claim 22 wherein R₁ in the nonpolar monomer is H or methyl and R₂ in the nonpolar monomer is COOM wherein M is a C₁₋₄ alkyl.

24. (Previously Added) The composition of claim 22 wherein R₁ is methyl and R₂ is COOM wherein M is butyl and the monomer is butyl methacrylate.

25. (Previously Added) The composition of claim 24 wherein the polar monomer R₁ is H or methyl, and R₂ is COOM wherein M is H.

26. (Previously Added) The composition of claim 24 wherein the polar monomer is acrylic acid or methacrylic acid.

27. (Previously Added) The composition of claim 1 wherein the polymer consists of a nonpolar monomer which is butyl methacrylate and a polar monomer which is acrylic acid and the acrylic acid is present at about 2-29% by weight of the total polymer.

28. (New) A nail enamel composition comprising, by weight of the total composition:

10-95% solvent, and

5-95% of a copolymer capable of forming a film on the nail, having a glass transition temperature in the range of 5 to 90° C., and consisting of butyl methacrylate copolymerized with a polar monomer selected from the group consisting of acrylic acid, methacrylic acid, and mixtures thereof.

29. (New) The composition of claim 28 wherein the copolymer consists of 2-29% by weight of the total copolymer of acrylic acid, with the remainder of the copolymer being butyl methacrylate.

30. (New) The composition of claim 28 wherein the copolymer consists of 2-29% by weight of the total polymer of methacrylic acid, with the remainder of the copolymer being butyl methacrylate.

31. (New) A nail enamel composition comprising, by weight of the total composition:

10-95% solvent, and

5-95% of a copolymer capable of forming a film on the nail, having a glass transition temperature in the range of 5 to 90° C., and consisting of methyl methacrylate polymerized with a

polar monomer selected from the group consisting of acrylic acid, methacrylic acid, and mixtures thereof.

32. (New) The nail enamel composition of claim 31 wherein the copolymer consists of 2-29% by weight of the total polymer of acrylic acid, with the remainder of the copolymer being methyl methacrylate.

33. (New) A nail enamel composition comprising, by weight of the total composition:

10-95% solvent, and

5-95% of a copolymer capable of forming a film on the nail, having a glass transition temperature in the range of 5 to 90° C., and consisting of a nonpolar monomer selected from the group consisting of methyl methacrylate, butyl methacrylate, and mixtures thereof; polymerized with a polar monomer selected from the group consisting of acrylic acid, methacrylic acid, and mixtures thereof.

34. (New) The composition of claim 33 wherein the copolymer consists of 2-29% of a polar monomer selected from the group consisting of acrylic acid, methacrylic acid, and mixtures thereof, with the remainder of the copolymer being a nonpolar monomer selected from the group consisting of butyl methacrylate, methyl methacrylate, and mixtures thereof.

35. (New) A method for polishing the nails comprising:

(a) applying to the nails a first composition comprising, by weight of the total composition:

10-95% solvent, and

5-95% of a film forming polymer having a glass transition temperature in the range of 5 to 90° C., and consisting of a nonpolar monomer selected from the group consisting of methyl methacrylate, butyl methacrylate, and mixtures thereof; copolymerized with a polar monomer selected from the group consisting of acrylic acid, methacrylic acid, and mixtures thereof.

(b) applying to the nails a second composition comprising, by weight of the total composition:

1-99% solvent, and

1-99% of a cellulose film forming polymer; wherein the dried film formed by (a) and (b) resides on the nails for five to ten days.

36. (New) The method of claim 35 wherein the cellulose film forming polymer comprises nitrocellulose.